

Nanometrics Introduces the IMPULSE+ Integrated Metrology System for Critical Dimension and Thin Film Process Control

Fleet Adoption across Several Leading 3D-NAND Device Manufacturers

MILPITAS, Calif., June 09, 2016 (GLOBE NEWSWIRE) -- Nanometrics Incorporated (NASDAQ:NANO), a leading provider of advanced process control systems, today announced the launch of IMPULSE[®]+, its latest system for integrated process control enabling both optical critical dimension (OCD) and thin film metrology. The IMPULSE+ has already been deployed for high-volume manufacturing of second-generation 3D-NAND as well as development of third-generation devices.

"Many of our customers have traditionally relied upon thin film measurements for chemical mechanical polish (CMP) control, and are now migrating to OCD technology for better correlation to device performance and yield," commented Dr. Srinivasa Vedula, vice president of OCD/Thin Film Solutions at Nanometrics. "Beginning with our 3D-NAND launch partner, the enhanced performance and features of the IMPULSE+ have driven rapid adoption, acceptance and deployment by multiple customers. With best-in-class deep-ultraviolet (DUV) optics and improvements in productivity, IMPULSE+ offers both maximum sensitivity and accuracy to detect CMP process excursions. Additionally, our existing customer investments in process equipment and metrology can be extended by enabling seamless field upgrades from IMPULSE to IMPULSE+."

The IMPULSE+ works in conjunction with Nanometrics' NanoDiffract[®] software suite, for critical dimension modeling and control as well as part of a larger fleet of IMPULSE, Trajectory[™] T3, and Atlas[®] family of systems to provide comprehensive fab-wide control. Nanometrics is the industry pioneer in integrated metrology with the broadest suite of offerings qualified on platforms for CMP, deposition, lithography track and etch systems. The IMPULSE+ can be deployed across key steps in DRAM, 3D-NAND, CMOS image sensor, and foundry/logic devices.

About Nanometrics

Nanometrics is a leading provider of advanced, high-performance process control metrology and inspection systems used primarily in the fabrication of semiconductors and other solid-state devices, including sensors, optoelectronic devices, high-brightness LEDs, discretes and data storage components. Nanometrics' automated and integrated metrology systems measure critical dimensions, device structures, topography and various thin film properties, including three-dimensional features and film thickness, as well as optical, electrical and material properties. The company's process control solutions are deployed throughout the fabrication process, from front-end-of-line substrate manufacturing, to high-volume production of semiconductors and other devices, to advanced three-dimensional wafer-level packaging applications. Nanometrics' systems enable advanced process control for device manufacturers, providing improved device yield at reduced manufacturing cycle time, supporting the accelerated product life cycles in the semiconductor and other advanced device markets. The company maintains its headquarters in Milpitas, California, with sales and service offices worldwide. Nanometrics is traded on NASDAQ Global Select Market under the symbol NANO. Nanometrics' website is <http://www.nanometrics.com>.

Forward Looking Statements

Certain statements in this press release are forward-looking statements that involve a number of risks and uncertainties that could cause actual results to differ materially from those described in this release. Although Nanometrics believes that the expectations reflected in the forward-looking statements are reasonable, actual results could differ materially from these expectations due to a variety of factors, including, but not limited to, shifts in the timing of product deliveries, the failure to achieve improved processes, the rate of adoption of our products, customer spending plans, and general economic conditions. For additional information and considerations regarding the risks faced by Nanometrics that could cause actual results to differ materially, see its annual report on Form 10-K for the year ended December 26, 2015, as filed with the Securities and Exchange Commission on February 24, 2016, including under the caption "Risk Factors," as well as other periodic reports filed with the SEC from time to time. Nanometrics disclaims any obligation to update information contained in any forward-looking statement, except as required by law.

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